



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Miwa KOZAWA et al.**

Group Art Unit: **1756**

Application Number: **10/720,097**

Examiner: **Daborah Chacko Davis**

Filed: **November 25, 2003**

Confirmation Number: **4454**

For: **PROCESS FOR FORMING RESIST PATTERN, SEMICONDUCTOR
DEVICE AND FABRICATION THEREOF**

Attorney Docket Number: **032132**

Customer Number: **38834**

RESPONSE UNDER 37 C.F.R. § 1.111

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

May 11, 2007

Sir:

In response to the Office Action dated January 11, 2007, the response date of which having been extended by one month to May 11, 2007, Applicants submit the following remarks, which begin on page 2 of this paper.